



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Docket No.: VLSI-3402.DIV.1 (US008032)

I hereby certify that this transmittal of the below described document is being deposited with the United States Postal Service in an envelope bearing First Class Postage and addressed to the Assistant Commissioner for Patents, Washington, D.C., 20231, on the below date of deposit.			
Date of Deposit:	11/5/01	Name of Person Making the Deposit:	Karen Yarr
		Signature of the Person Making the Deposit:	<i>Karen Yarr</i>

Inventor(s): ANNAPRAGADA

Serial No.: 09/902,056

Group Art Unit: 2812

Filed: 7/9/01

Examiner: Not yet assigned

Title: A METHOD OF IMPROVING ADHESION OF CAP OXIDE TO NANOPOROUS SILICA FOR INTEGRATED CIRCUIT FABRICATION

The Assistant Commissioner for Patents

Washington, D.C. 20231

Sir:

Certification for PTO Consideration of an Information Disclosure Statement  
(Under 37 CFR §1.97)

Consideration of the enclosed Information Disclosure Statement is requested.

1. This certification is being made for this information disclosure statement

☒ [ X ] accompanying this certification

☐ [ ] Filed \_\_\_\_\_

2. I hereby certify that:

- ☒ X Each item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the statement.
- ☐ No item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart application, or, to the knowledge of the person signing certification after making reasonable inquiry, was known to any individual designated in §1.56(c) more than three months prior to the filing of the statement.

3. The person making this certification is

☒ [ x ] a person who is substantively involved in the preparation or prosecution of the application, and who is associated with the inventor, with the assignee, or with anyone to whom there is an obligation to assign the application (37 C.F.R. 1.56 (c)) and who signs below.

☐ [ ] the inventor(s) who signs below

☐ [ ] the practitioner who signs below on the basis of the information:

☐ [ ] supplied by the inventors

☐ [ ] supplied by an individual designated in § 1.56(c)

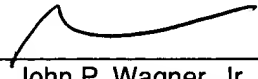
☐ [ ] in the practitioners file

Please direct all correspondence concerning the above-identified application to the following address:

**WAGNER, MURABITO & HAO LLP**  
Two North Market Street, Third Floor  
San Jose, California 95113  
(408) 938-9060

Respectfully submitted,

Date: 11/05/01

By:   
John P. Wagner, Jr.  
Reg. No. 35,398



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney Docket No.: VLSI-3402 DIV. 1 (US008032)

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The Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Sir:

Information Disclosure Statement Submitted Pursuant to 37 C.F.R. 1.97(b)

The citations referenced herein, copies attached, may be material to the examination of the above-identified application and are, therefore, submitted in compliance with the duty of disclosure as defined in 37 C.F.R. 1.56. The Examiner is requested to make these citations of official record in the application.

This Information Disclosure Statement submitted in accordance with 37 C.F.R. 1.97(b) is not to be construed as a representation that a search has been made, that additional items material to the examination of this application do not exist, or that any one or more of these citations constitute prior art under 35 U.S.C. 102.

The Examiner's attention is respectfully directed to the following U.S. Patents:

<u>Pat. No.</u>	<u>Pat. Title</u>	<u>Grant Date</u>
<b>Foreign Patent or Published Foreign Patent Application</b>		
EPO 687004A1	METHOD FOR FABRICATION OF DIELECTRICS ON SEMICONDUCTOR DEVICES	12/13/95
EPO 881678A2	IMPROVEMENTS IN OR RELATING TO POROUS DIELECTRIC STRUCTURES	12/2/98
EPO 884401A1	METHOD AND SYSTEM FOR COATING THE INSIDE OF A PROCESSING CHAMBER	12/16/98
WO 98/47177	NANOPOROUS DIELECTRIC FILMS WITH GRADED DENSITY AND PROCESS FOR MAKING SUCH FILMS	10/22/98

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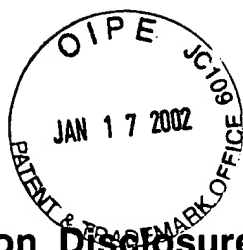
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Patent

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## Information Disclosure Statement Transmittal

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Date of Deposit:	11/5/01	Name of Person Making the Deposit:	Karen Yarr	Signature of the Person Making the Deposit:	<i>Karen Yarr</i>
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Serial No.: 09/902,056

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The Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Sir:

## Information Disclosure Statement Transmittal

Transmitted herewith is the following:

..... Formal drawings, totaling ..... sheets.  
..... Informal drawings, totaling ..... sheets.  
☒ Certification for PTO Consideration  
☒ Information Disclosure statement ( 1 sheets)  
..... Information Disclosure statement and late filing fee  
☒ Form 1449  
..... Petition for Extension of Time  
..... Other: .....

## F Calculation (for other than a small entity)

Fee Items	Fee Rate	Total
Petition for Extension of Time (fee calculated elsewhere)	\$ .00	0.00
Information Disclosure Statement, late filing	\$240.00	0.00
Other:		0.00
<b>Total Fees</b>		<b>0.00</b>

## PAYMENT OF FEES

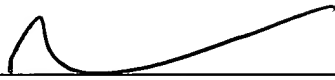
1. The full fee due in connection with this communication is provided as follows:
- [ ] The Commissioner is hereby authorized to charge any additional fees associated with this communication or credit any overpayment to Deposit Account No.: 23-0085.  
A duplicate copy of this authorization is enclosed.
- [ ] A check in the amount of \$
- [X] Charge any fees required or credit any overpayments associated with this filing to Deposit Account No.: 23-0085.

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